

Fig. 1

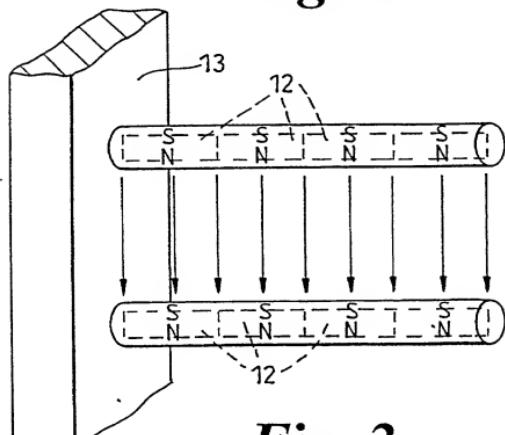


Fig. 2

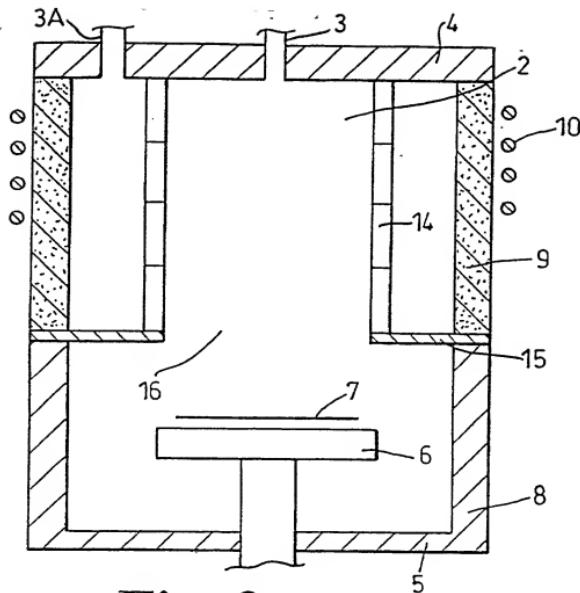


Fig. 3

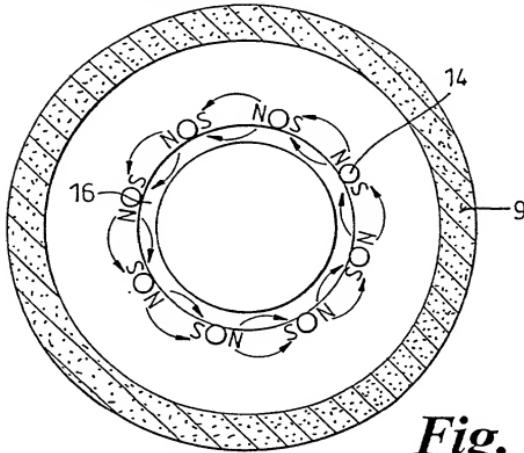
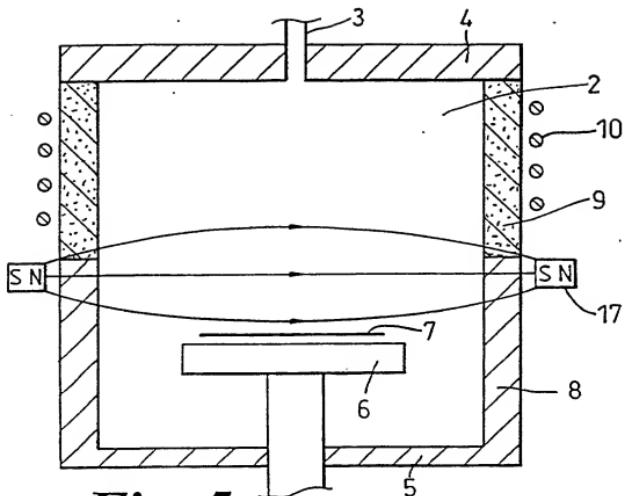
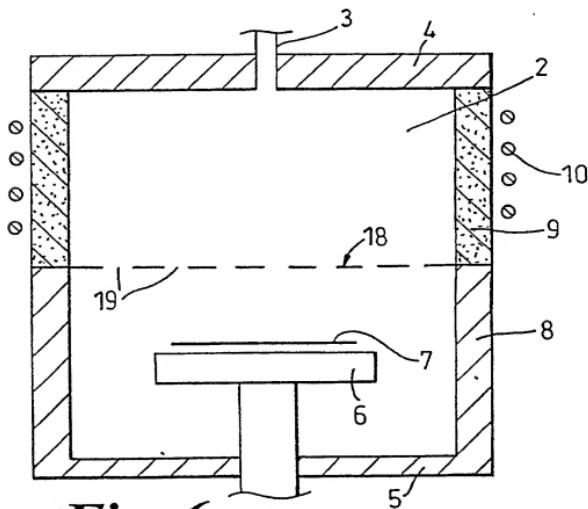


Fig. 4



<divFigFig. 5.!!



<divFigFig. 6!!

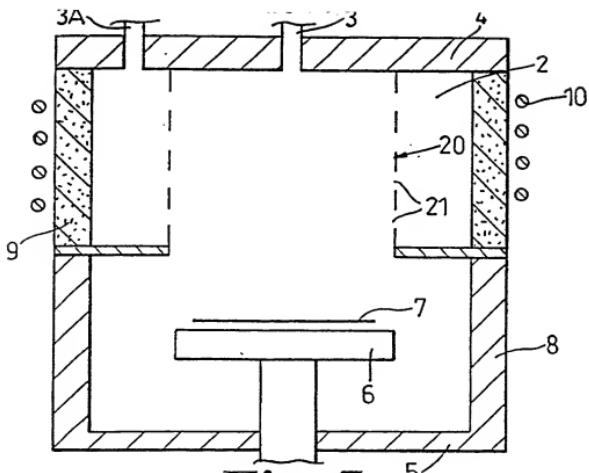


Fig. 7

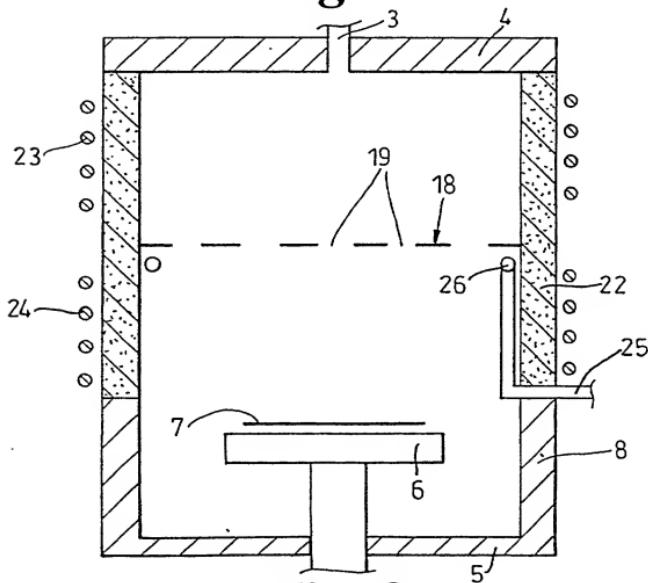


Fig. 8

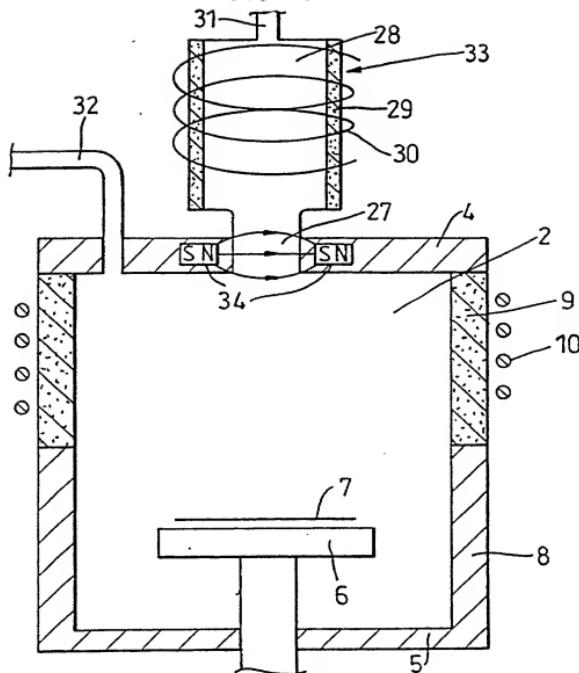
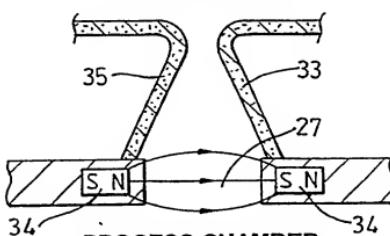


Fig. 9

PULSED SOURCE



PROCESS CHAMBER

Fig. 10

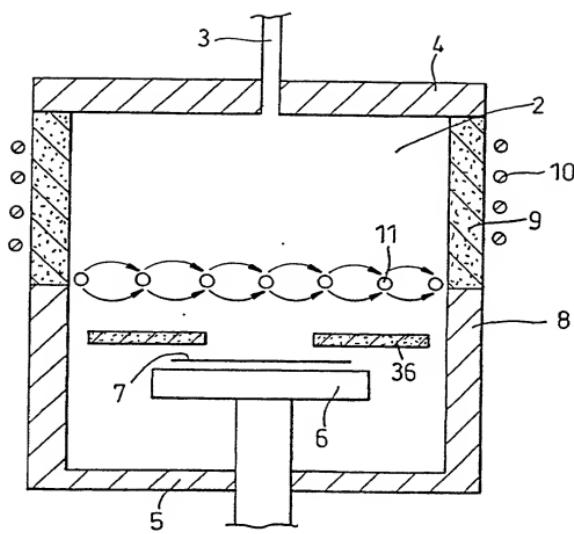


Fig. 11

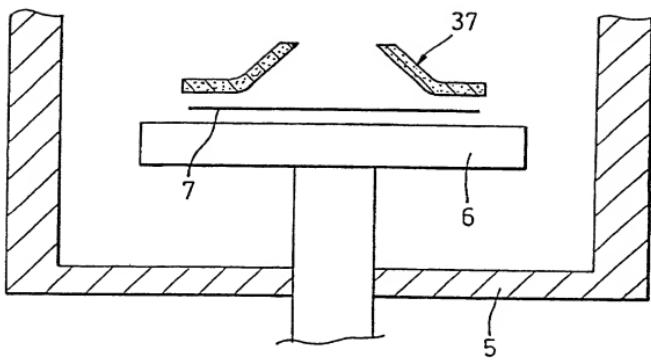


Fig. 12A

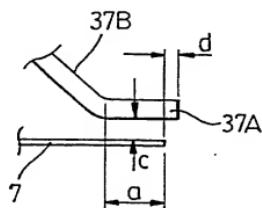


Fig. 12B

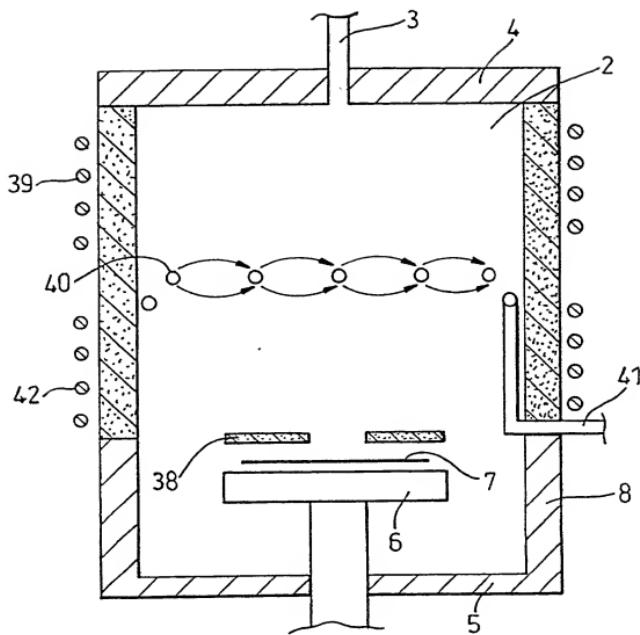


Fig. 13

EFFECT OF MAGNETIC ATTENUATOR

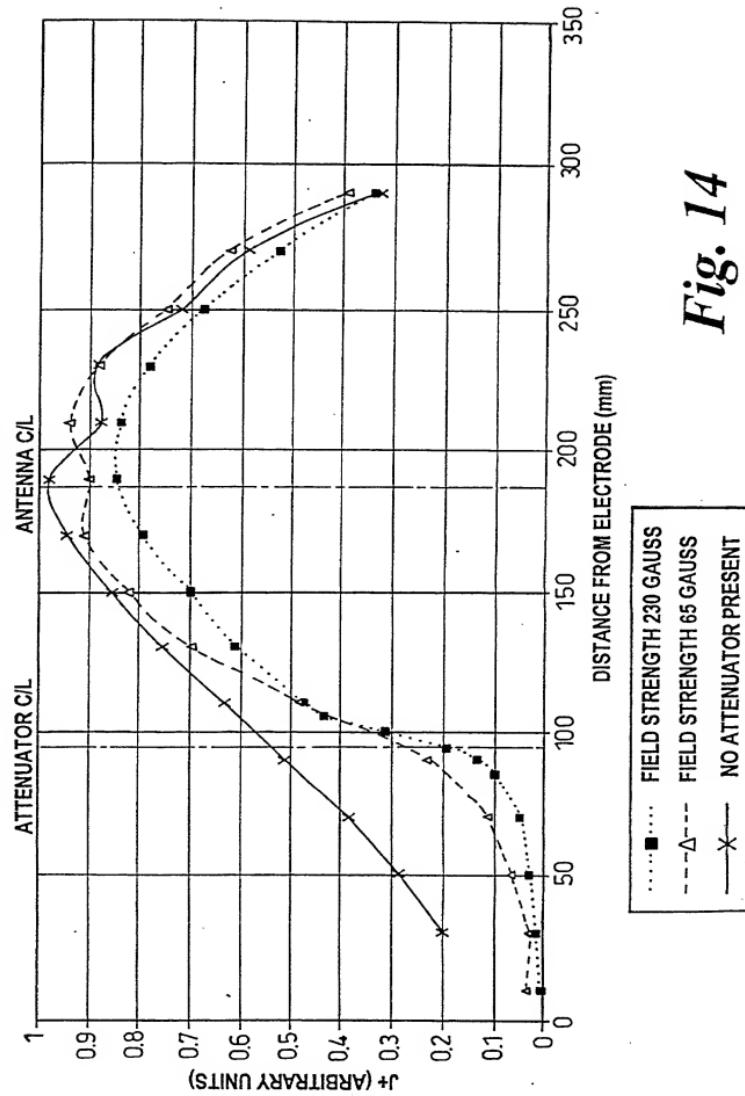


Fig. 14

MAGNETIC ATTENUATOR POWER VARIATION 20mT SF6 FIELD STRENGTH 230 GAUSS

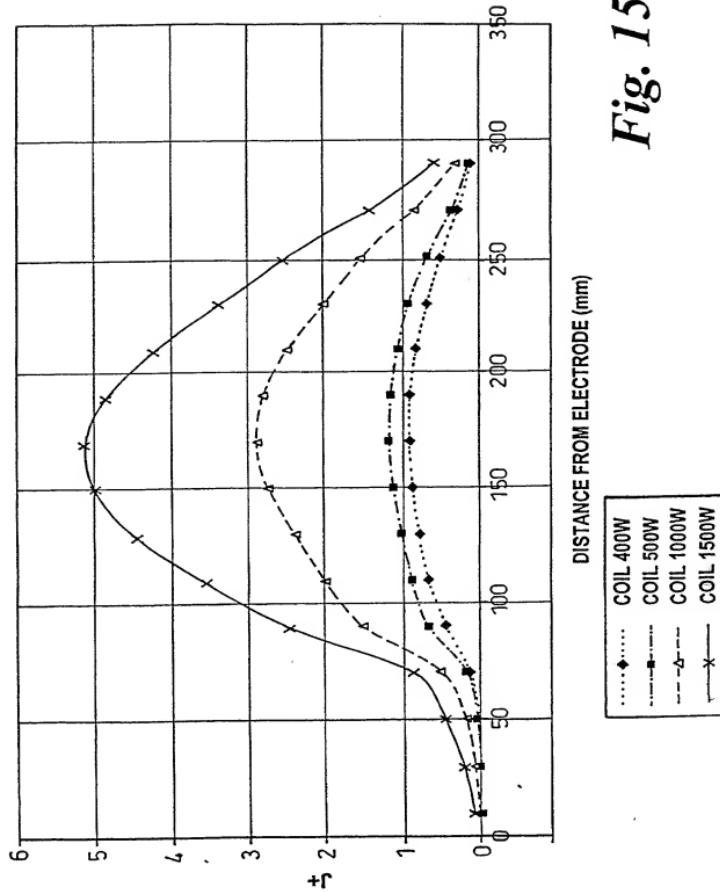


Fig. 15

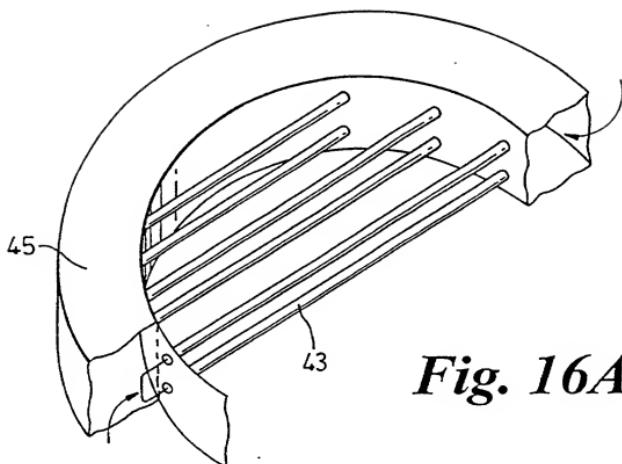


Fig. 16A

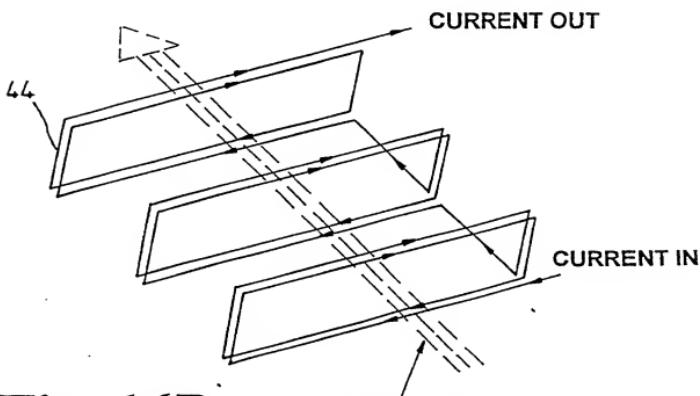


Fig. 16B MAGNETIC FIELD

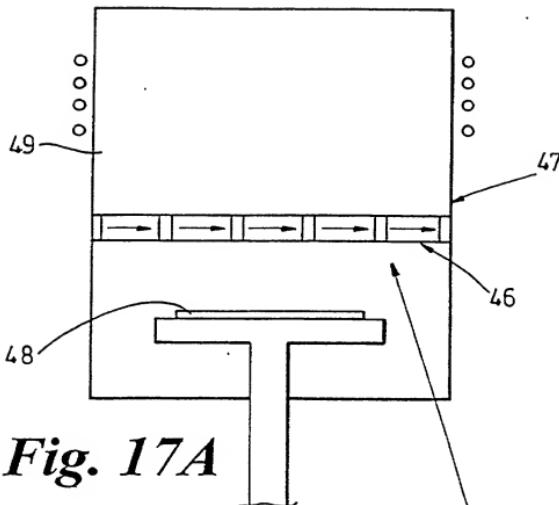


Fig. 17A

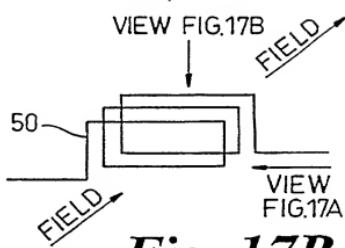


Fig. 17B

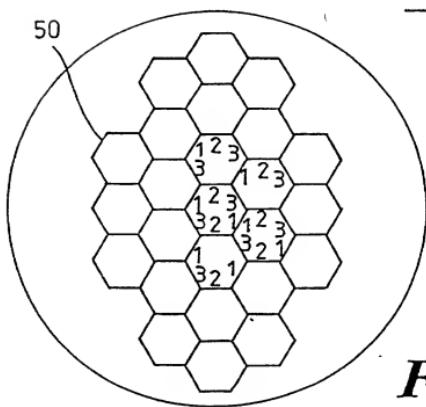


Fig. 17C

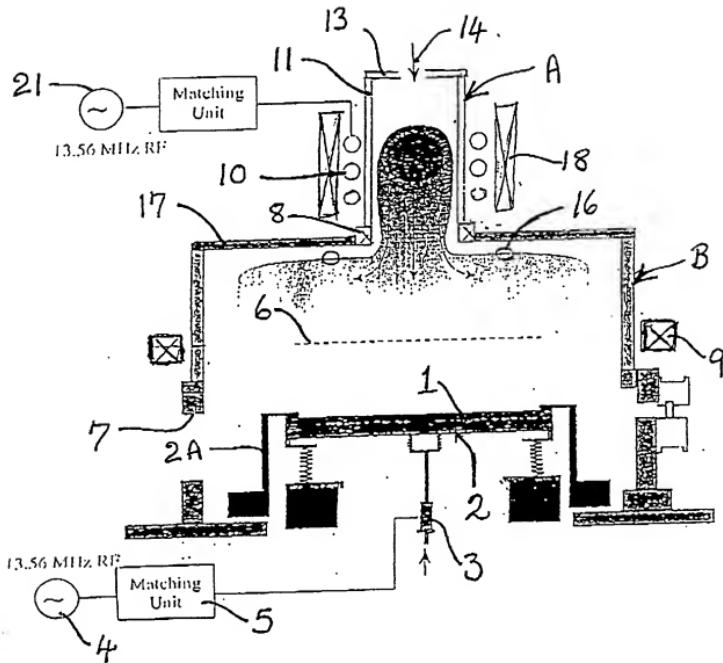


Fig. 18

Fig. 19

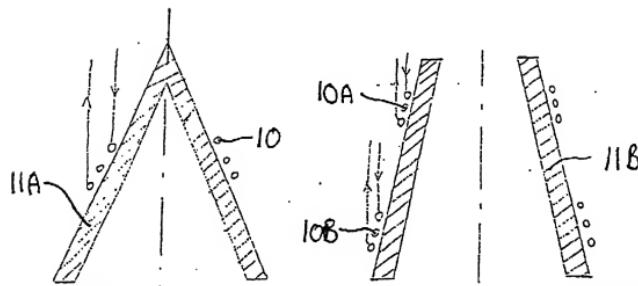
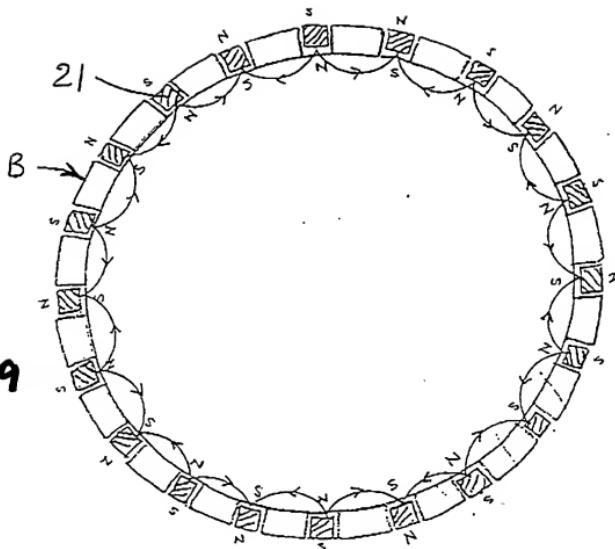


FIG. 20A

FIG. 20B

FIG. 20C

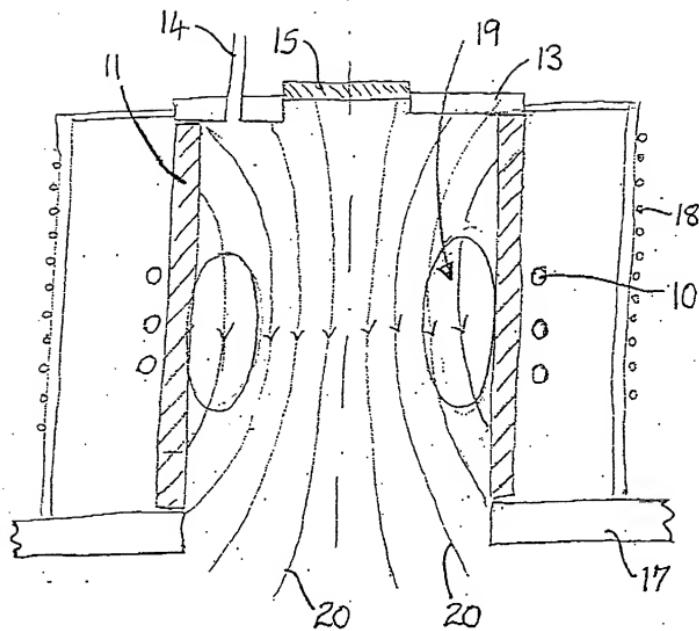


FIG. 21

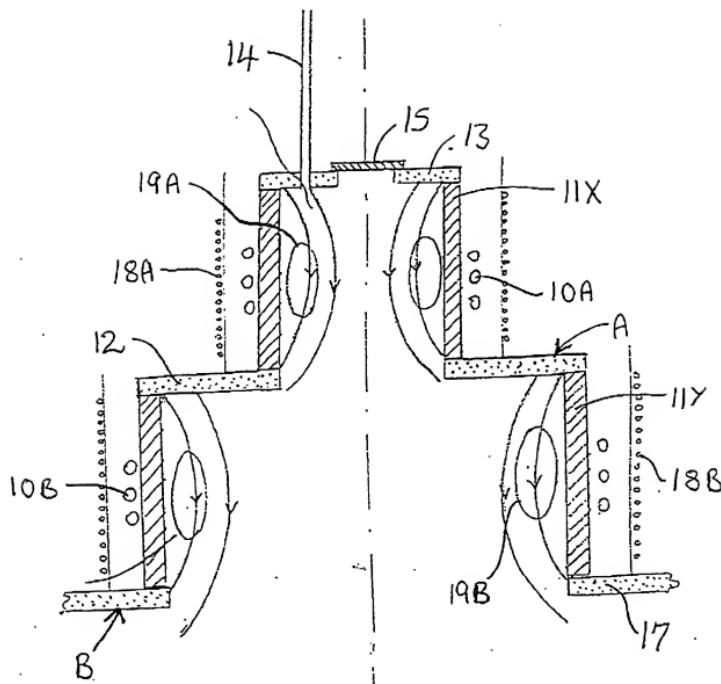


FIG. 22

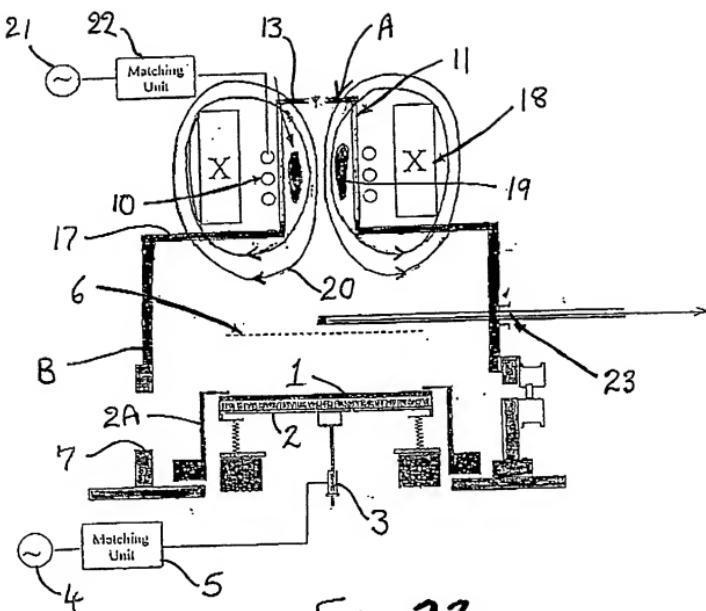


FIG. 23

Results from Langmuir probe. Constant gas flow, pressure, RF power into plasma

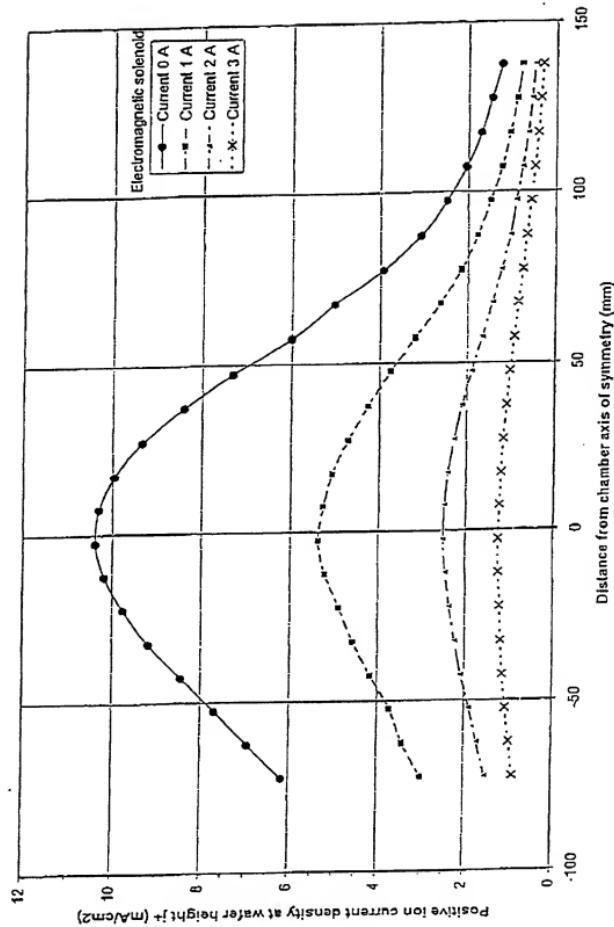


FIG. 24

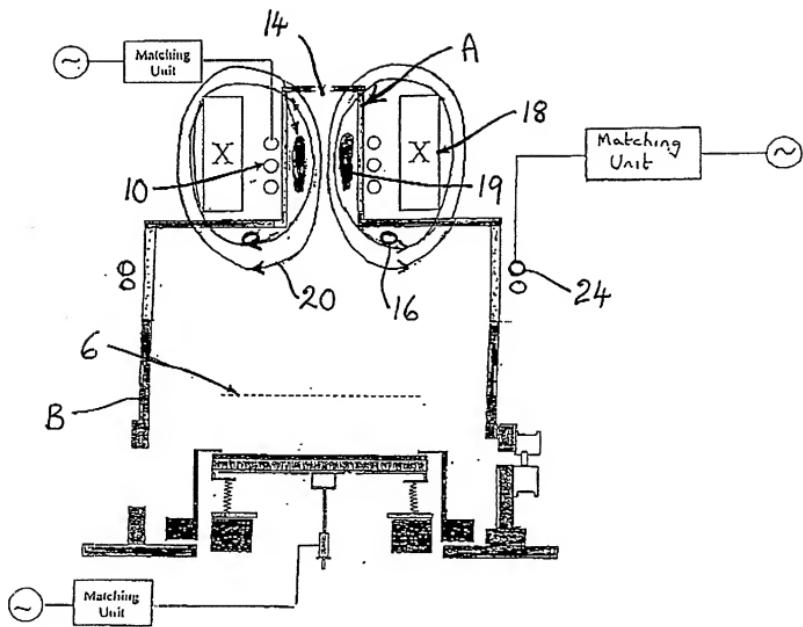


FIG. 25

